

East USPTO USPTW PTD JPO

L Number	Hits	Search Text	DB	Time stamp
1	153104	polish\$ or chemipolish\$ or chemimech\$ or cmp	USPAT; US-PGPUB	2004/08/16 13:14
2	212237	planariz\$ or lap\$	USPAT; US-PGPUB	2004/08/16 13:14
3	178051	grind\$ or abrad\$	USPAT; US-PGPUB	2004/08/16 13:14
4	301710	silica or "si2o3" or ("si.sub.2" with "o.sub.3")	USPAT; US-PGPUB	2004/08/16 13:14
5	354557	calcium strontium or barium	USPAT; US-PGPUB	2004/08/16 13:15
6	908510	ca or sr or ba	USPAT; US-PGPUB	2004/08/16 13:15
8	389845	alk or alkal\$	USPAT; US-PGPUB	2004/08/16 13:15
9	1826	((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))	USPAT; US-PGPUB	2004/08/16 12:35
10	270	((alk or alkal\$) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))	USPAT; US-PGPUB	2004/08/16 12:35
11	905	((polish\$ or chemipolish\$ or chemimech\$ or cmp) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))	USPAT; US-PGPUB	2004/08/16 12:35
12	229	((alk or alkal\$) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))))	USPAT; US-PGPUB	2004/08/16 12:36
13	53	((polish\$ or chemipolish\$ or chemimech\$ or cmp) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))) same ph	USPAT; US-PGPUB	2004/08/16 12:36
14	17	((alk or alkal\$) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same ph)	USPAT; US-PGPUB	2004/08/16 12:38

30	29	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))) and (438.clas. or 216.clas.)) not (((((alk or alkal\$) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same ph)) and (semiconduct\$ or wafer or chip)) or (((polish\$ or chemipolish\$ or chemimech\$ or cmp) same (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba)))) same ph))) same ph)	USPAT; US-PGPUB	2004/08/16 13:10
31	4	(((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) same (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) same ((calcium strontium or barium) or (ca or sr or ba))) and (438.clas. or 216.clas.)) and 252.clas.	USPAT; US-PGPUB	2004/08/16 13:10
32	105087	polish\$ or chemipolish\$ or chemimech\$ or cmp	JPO;	2004/08/16 13:47
33	88045	planariz\$ or lap\$	DERWENT	2004/08/16 13:14
34	134237	grind\$ or abrad\$	JPO;	2004/08/16 13:14
35	136824	silica or "si2o3" or ("si.sub.2" with "o.sub.3")	DERWENT	2004/08/16 13:40
36	162693	calcium strontium or barium	JPO;	2004/08/16 13:39
37	1464820	ca or sr or ba	DERWENT	2004/08/16 13:39
38	356665	alk or alkal\$	JPO;	2004/08/16 13:15
39	412403	ph or phs	DERWENT	2004/08/16 13:16
40	820	((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and ((calcium strontium or barium) or (ca or sr or ba))	JPO;	2004/08/16 13:39
41	212	(((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and ((calcium strontium or barium) or (ca or sr or ba))) and ((alk or alkal\$) or (ph or phs))	DERWENT	2004/08/16 13:18
42	1164919	semiconduct\$ or wafer or chip	JPO;	2004/08/16 13:18
44	77	(((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and ((calcium strontium or barium) or (ca or sr or ba))) and (semiconduct\$ or wafer or chip)	DERWENT	2004/08/16 13:18

43	42	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and ((calcium strontium or barium) or (ca or sr or ba))) and ((alk or alkal\$) or (ph or phs))) and (semiconduct\$ or wafer or chip)	JPO; DERWENT	2004/08/16 13:19
45	35	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and ((calcium strontium or barium) or (ca or sr or ba))) and (semiconduct\$ or wafer or chip)) not (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and ((calcium strontium or barium) or (ca or sr or ba))) and ((alk or alkal\$) or (ph or phs))) and (semiconduct\$ or wafer or chip)) (calcium strontium or barium).ti,ab.	JPO; DERWENT	2004/08/16 13:30
46	161450	(ca or sr or ba).ti,ab.	JPO; DERWENT	2004/08/16 13:39
47	147087	(ca or sr or ba).ti,ab.	JPO; DERWENT	2004/08/16 13:39
48	441	((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))	JPO; DERWENT	2004/08/16 13:39
49	438	((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.	JPO; DERWENT	2004/08/16 13:41
50	27	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (ph or phs).ti,ab.	JPO; DERWENT	2004/08/16 13:41
51	21	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (alkalin\$).ti,ab.	JPO; DERWENT	2004/08/16 13:41
52	42	(((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (ph or phs).ti,ab.) or (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (alkalin\$).ti,ab.)	JPO; DERWENT	2004/08/16 13:41
53	260677	"53" not (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium) or (ca or sr or ba))) and (semiconduct\$ or wafer or chip))	JPO; DERWENT	2004/08/16 13:41

54	42	(((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (ph or phs).ti,ab.) or (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (alkalin\$).ti,ab.) not (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium) or (ca or sr or ba))) and (semiconduct\$ or wafer or chip))	JPO; DERWENT	2004/08/16 13:46
55	396	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) not (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (ph or phs).ti,ab.) or (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (alkalin\$).ti,ab.) not (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (((calcium strontium or barium) or (ca or sr or ba))) and (semiconduct\$ or wafer or chip)))	JPO; DERWENT	2004/08/16 13:46
56	350	((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) not (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (ph or phs).ti,ab.) or (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (alkalin\$).ti,ab.) not (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3").ti,ab.) and (((calcium strontium or barium) or (ca or sr or ba))) and (semiconduct\$ or wafer or chip))) not (oral teeth or tooth or dental or dentrif\$)	JPO; DERWENT	2004/08/16 13:46

57	350	(((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) not ((((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (ph or phs).ti,ab.) or (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (alkalin\$).ti,ab.)) not (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium) or (ca or sr or ba)) and (semiconduct\$ or wafer or chip)))) not (oral or teeth or tooth or dental or dentrif\$)	JPO; DERWENT	2004/08/16 13:47
58	31	(((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) not ((((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (ph or phs).ti,ab.) or (((((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium).ti,ab.) or ((ca or sr or ba).ti,ab.))) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")).ti,ab.) and (alkalin\$).ti,ab.)) not (((polish\$ or chemipolish\$ or chemimech\$ or cmp) or (planariz\$ or lap\$) or (grind\$ or abrad\$)) and (silica or "si2o3" or ("si.sub.2" with "o.sub.3")) and (((calcium strontium or barium) or (ca or sr or ba)) and (semiconduct\$ or wafer or chip)))) not (oral or teeth or tooth or dental or dentrif\$) and (polish\$ or chemipolish\$ or chemimech\$ or cmp).ti.	JPO; DERWENT	2004/08/16 13:53

STN8 Caplus

(FILE 'HOME' ENTERED AT 10:20:33 ON 16 AUG 2004)

FILE 'CAPLUS' ENTERED AT 10:20:44 ON 16 AUG 2004

L1 198792 S CMP OR ?POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR GRIND?
L2 1478444 S CA OR CALCIUM OR SR OR STRONTIUM OR BA OR BARIUM
L3 13811 S L1 AND L2
L4 443516 S SILICA OR SI2O3
L5 1217 S L3 AND L4

FILE 'REGISTRY' ENTERED AT 10:21:37 ON 16 AUG 2004

FILE 'REGISTRY' ENTERED AT 10:21:42 ON 16 AUG 2004
L6 1839 S SILICA/CNS

FILE 'CAPLUS' ENTERED AT 10:21:52 ON 16 AUG 2004

L7 1177 S L3 AND L6
L8 1432 S L5 OR L7
L9 4520 S FUMED
L10 19 S L8 AND L9
L11 ~171 S L8 AND (WAFER? OR SEMICONDUCT? OR CHIP?)
L12 171 S L11 NOT L10
L13 53 S L12 AND (?POLISH? OR CHEMIMECH? OR PLANARIZ? OR CMP OR GRIND?)
L14 118 S L12 NOT L13
L15 5 S L14 AND PH
L16 113 S L14 NOT L15
L17 42 S L16 AND (METHOD OR PROCESS)/TI
L18 71 S L16 NOT L17
L19 2 S L18 AND SLURR?
L20 69 S L18 NOT L19
SAVE POLISHL20/A L20
L21 102 S L8 AND PH
L22 84 S L21 NOT L11
SAVE POLISHL22/A L22